

Structural analysis of expanded stacking faults in 4H-SiC bipolar devices

Silicon carbide (SiC) is the next candidate in power semiconductor materials. A forward-current degradation in 4H-SiC bipolar devices is one of the most crucial issue. The degradation caused by the expansion of stacking faults (SFs). We introduces structural analysis of the SF expansion origin using S/TEM observation.

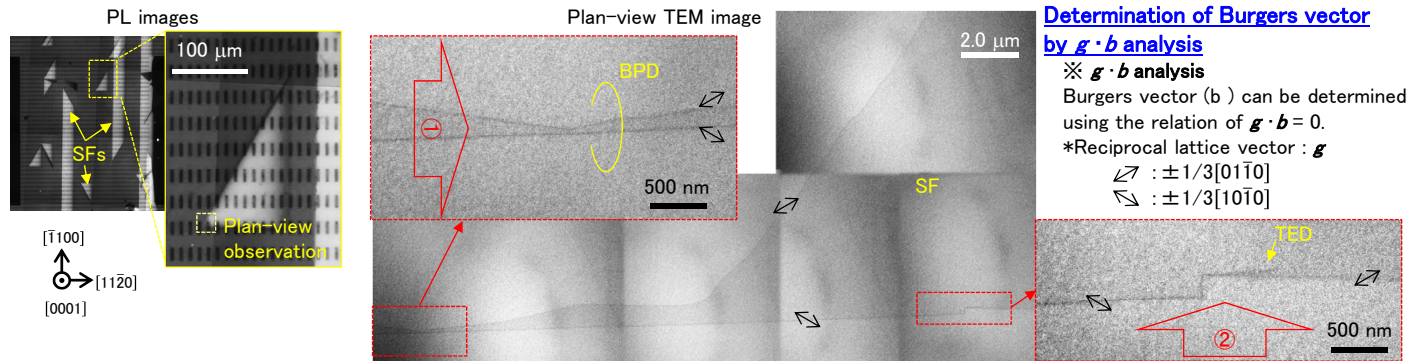
[Sample] 4H-SiC pin diode (4° off-cut, Epitaxial layer: 10 μm)

Reference:

S. Hayashi, et. al., Appl. Phys. Express **10**, 081201 (2017).
 S. Hayashi, et. al., Jpn. J. Appl. Phys. **57**, 04FR07 (2018).
 S. Hayashi, et. al., Appl. Phys. Express **12**, 051007 (2019).

1. Plan view TEM observation of SF expansion origin

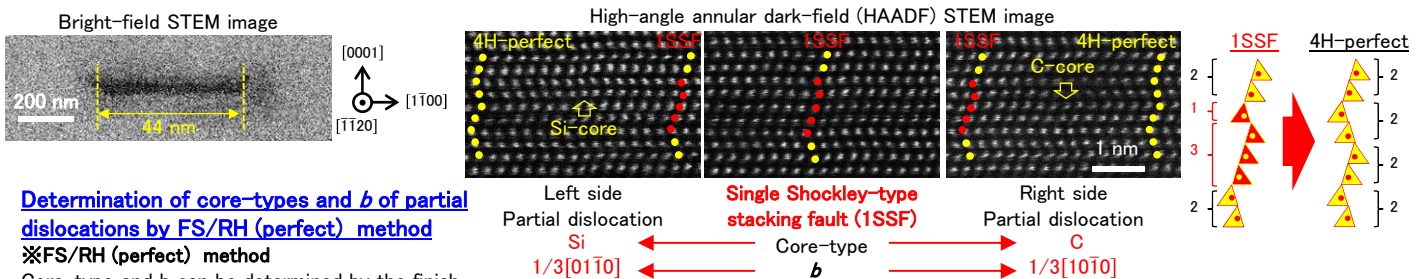
◆ The area near a 1SSSF expansion origination point was observed by plan-view TEM.



Both ① basal -plane dislocation (BPD) and ② threading edge dislocation (TED) were observed.
 ⇒ The SF expanded from BPD converted into TED near the epi./sub. interface.

2. Observation of the cross section ① near BPD

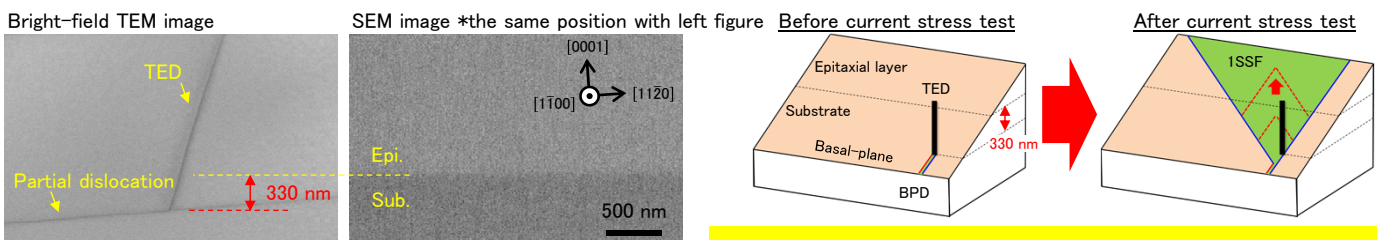
◆ Core-types and b of partial dislocations were investigated by cross-sectional STEM observation in high-spatial resolution.



The b of BPD is $b = 1/3[11\bar{2}0]$, and BPD are composed of 1SSSF and two Shockley partial dislocations of Si- and C-core.

3. Observation of the cross section ② near TED

◆ Depth of BPD-TED conversion was investigated by combination of cross-sectional TEM and SEM images.



BPD-TED conversion depth was measured by TEM and SEM images of same cross-section.

The origin was BPD converted into TED in substrate. 1SSSF expanded by migration of Si-core partial dislocation

A combination between plan-view and cross-sectional view S/TEM observations yields us some information about expansion mechanism of stacking fault!

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